

 <p><b>INFORMATION DISCLOSURE STATEMENT</b></p> <p><b>BY APPLICANT</b></p>	Docket: 6047-53173	App: 09/590 795
	Applicant: Vishnu K. Agarwal et al.	
	Filed: June 8, 2000	Art Unit:

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**U.S. PATENT DOCUMENTS**

Init.*	Number	Date	Name	Class	Sub	Filed
DV	6,060,367 ✓	5/9/00	Sze			
	6,060,351 ✓	5/9/00	Parekh et al.			
	6,049,101 ✓	4/11/00	Graettinger et al.			
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	6,015,743 ✓	1/18/00	Zahurak et al.			
	5,962,065 ✓	10/5/99	Weimer et al.			
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	5,427,974 ✓	6/27/95	Lur et al.			
	5,372,962 ✓	12/13/94	Hirota et al.			
	5,342,800 ✓	8/30/94	Jun			
DV	5,318,920 ✓	6/7/94	Hayashide			

EXAMINER: *Bhuland*

DATE *09/27/01*

\*Examiner: Initial if considered, whether or not in conformance with MPEP 60;  
draw line through cite if not in conformance and not considered. Send copy.

<div style="display: flex; align-items: center;"> <div style="border: 1px solid black; border-radius: 50%; padding: 10px; text-align: center; margin-right: 10px;"> <b>O I P E</b>              SEP 12 2000              PATENT &amp; TRADEMARK OFFICE           </div> <div> <b>INFORMATION DISCLOSURE STATEMENT</b>              BY APPLICANT           </div> </div>				Docket: 6047-53173		App: 09/590,795	
				Applicant: Vishnu K. Agarwal et al.			
				Filed: June 8, 2000		Art Unit:	
<b>U.S. PATENT DOCUMENTS</b>							
Init.*		Number	Date	Name	Class	Sub	Filed
DV		5,130,885✓	7/14/92	Fazan et al.	X	X	—
DV		5,068,199✓	11/26/91	Sandhu			—
<b>FOREIGN PATENT DOCUMENTS</b>							
		Number	Date	Country	Class	Sub	
<b>OTHER DOCUMENTS</b>							
DV			Kawahara, Takaaki et al., "(Ba, Sr)TiO <sub>3</sub> Films Prepared by Liquid Source Chemical Vapor Deposition on Ru Electrodes," <u>Jpn. J. Appl. Phys.</u> , <u>35</u> :4880-4885 (1996).				
EXAMINER:			<i>fvuland</i>				
DATE			09/27/01				
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# INFORMATION DISCLOSURE STATEMENT

BY APPLICANT

Docket: 6047-53173

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Applicant: Agarwal et al.

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Art Unit: 2811

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Init.*	Number	Date	Name	Class	Sub	Filed
DV	5,852,307	12/22/98	Aoyama et al.			

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## OTHER DOCUMENTS

DV	Kaga et al., "Thermal Stability of RuO <sub>2</sub> Thin Films and Effects of Annealing Ambient on Their Reduction Process," <u>Jpn. J. Appl. Phys.</u> 38:3689-3692 (June 15, 1999).
DV	Hayashide et al., "Fabrication of Storage Capacitance-Enhanced Capacitors with a Rough Electrode," <u>Jpn. J. Appl. Phys.</u> , pp. 869-872 (1990).
DV	Matsui et al., "Thermal Stability of a RuO <sub>2</sub> Electrode Prepared by DC Reactive Sputtering", <u>Jpn. J. Appl. Phys.</u> 39:256-263 (January 15, 2000).

EXAMINER: *Freeland*

DATE *09/25/02*

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# INFORMATION DISCLOSURE STATEMENT

BY APPLICANT

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Applicant: Agarwal et al.

Filed: June 8, 2000

Art Unit: 2811

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EXAMINER: *Andrzej*

DATE 03/19/03

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